

NEW French Nano-Imprint Lithography network and resources

Nouveau RÉseau National de la Lithographie par NanoImpression :

RÉNIL

INL / LTM / C2N / LAAS

Contact : contact@renil.fr

<http://www.renil.fr>

Keywords : Nanoimprint Lithography, processes, French resources

Nanoimprint lithography is an emergent and simple technology with high industrial potential thanks to its simplicity of implementation, the range of accessible dimensions (nanometric resolution, surface treatment up to several hundred cm²) and the associated low cost. Considering this “simplicity” of the process, it remains very dependent on the materials used and the fields of application targeted. Thus in French research laboratories, several experts work on the development of the process for large range of application domains : optic, health, optoelectronic, solar, spatial, telecom, etc...

The laboratories on the initiative of the RENIL network (INL, LTM, C2N, LAAS) care to open this one and federate a larger community. Through this presentation, we want to promote, at national scale, the nanoimprint technologies, share know-how, identify partners to meet the needs of a large number of potential users (academic or private). The presentation is oriented towards all actors of micro and nanotechnologies with good knowledge or wishing to know more about the technique, various applications and materials. A state of the art of progresses in research laboratories will be presented. The setting-up of RENIL Network will go through regular exchanges, like the J-NIL days help in 2021 [<https://inl.cnrs.fr/journee-nationale-sur-les-procedes-de-lithographie-par-nano-impression/>].